CLAIMS

What is claimed is.

- 1 1. A process comprising:
- 2 first forming an imprinted first polymer disposed upon a substrate under
- 3 conditions to increase the glass transition temperature (T_G) of the first polymer; and
- 4 subsequently thermal curing an imprinted subsequent polymer disposed over
- 5 the first polymer.
- 1 2. The process of claim 1, before subsequently thermal curing, the process
- 2 further including:
- 3 subsequently thermal imprinting the subsequent polymer, under conditions
- 4 to increase the T_G of the second polymer.
- 1 3. The process of claim 1, wherein subsequently thermal curing includes a
- 2 single thermal cure, selected from mircrowave radiation, infrared radiation, and
- 3 convection.
- 1 4. The process of claim 1, wherein first forming an imprinted first polymer
- 2 exposes a portion of the substrate.
- 1 5. The process of claim 1, wherein first forming an imprinted first polymer
- 2 exposes a portion of the substrate to form a first topology, further including:
- forming a first metallization within a recess in the first topology.
- 1 6. The process of claim 1, wherein subsequently thermal curing is carried out
- 2 under conditions to heat the subsequent polymer at a greater rate than the substrate.

- 1 7. The process of claim 1, further including:
- 2 first imprinting the first polymer to form a first topology, wherein first
- 3 imprinting exposes a portion of the substrate; and
- 4 subsequently imprinting the subsequent polymer to form a second topology,
- 5 wherein the second topology exposes a portion of the first polymer.
- 1 8. The process of claim 1, further including:
- 2 first imprinting the first polymer to form a first topology, wherein first
- 3 imprinting exposes a portion of the substrate;
- forming a first metallization within a recess in the first topology;
- subsequently thermal imprinting the subsequent polymer to form a second
- 6 topology, under conditions to increase the T_G of the second polymer, wherein the
- 7 second topology exposes a portion of the first polymer; and
- 8 forming a subsequent metallization within a recess in the subsequent
- 9 topology.
- 1 9. The process of claim 1, wherein the substrate includes an upper surface and
- 2 a lower surface, wherein the first polymer is disposed upon the upper surface,
- 3 wherein the first polymer includes a cured polymer upper first film, wherein the
- 4 second polymer includes a cured polymer upper second film, and upon the lower
- 5 surface, the process further including:
- first thermal curing a lower first polymer under conditions to heat the lower
- 7 first polymer at greater rate than the substrate; and
- 8 subsequently thermal curing an imprinted subsequent lower polymer
- 9 disposed over the lower first polymer.
- 1 10. The process of claim 1, wherein the first polymer is formed over the
- 2 substrate by depositing a prepolymer selected from a resin, a cyanate ester, a
- 3 polyimide, a polybenzoxazole, a polybenzimidazole, a polybenzothiazole, and
- 4 combinations thereof.

- 1 11. The process of claim 1, wherein the cured polymer first film includes a film-
- 2 to-substrate thickness ratio selected from about one-tenth, one-eighth, one-fifth,
- 3 one-fourth, one-third, and one-half the thickness of the substrate.
- 1 12. The process of claim 1, wherein the first polymer is formed over the
- 2 substrate by depositing a prepolymer selected from a resin, a cyanate ester, a
- 3 polyimide, a polybenzoxazole, a polybenzimidazole, a polybenzothiazole, and
- 4 combinations thereof, and wherein the cured polymer first film includes a film-to-
- 5 substrate thickness ratio selected from about one-tenth, one-eighth, one-fifth, one-
- 6 fourth, one-third, and one-half the thickness of the substrate.
- 1 13. The process of claim 1, further including:
- 2 in situ testing the substrate while attached as part of an array of substrates.
- 1 14. A process comprising:
- 2 first forming an imprinted first polymer disposed upon a substrate under
- 3 conditions to increase the glass transition temperature (T_G) of the first polymer;
- 4 second forming an imprinted second polymer upon the imprinted first
- 5 polymer to form a second topology including a second recess; and
- 6 subsequently thermal curing the imprinted subsequent polymer disposed
- 7 over the first polymer, wherein subsequently thermal curing forms a cured polymer
- 8 upper first film from the imprinted first polymer and a cured polymer upper second
- 9 film from the imprinted second polymer.
- 1 15. The process of claim 14, before second forming, further including:
- 2 forming a first conductive material in the first recess; and
- forming a second conductive material in the second recess.

- 1 16. The process of claim 14, further including:
- 2 forming a first conductive material in the first recess, wherein forming a first
- 3 conductive material is selected from blanket depositing and electroless plating; and
- 4 after second curing
- forming a second conductive material in the second recess, wherein forming
- 6 a second conductive material is selected from blanket depositing and electroless
- 7 plating.
- 1 17. The process of claim 14, wherein the first polymer is formed over the
- 2 substrate by depositing a prepolymer selected from a resin, a cyanate ester, a
- 3 polyimide, a polybenzoxazole, a polybenzimidazole, a polybenzothiazole, and
- 4 combinations thereof.
- 1 18. The process of claim 14, wherein the cured polymer first film is in a film-to-
- 2 substrate thickness ratio selected from about one-tenth, one-eighth, one-fifth, one-
- 3 fourth, one-third, and one-half the thickness of the substrate.
- 1 19. The process of claim 14, wherein the first polymer is formed over the
- 2 substrate by depositing a prepolymer selected from a resin, a cyanate ester, a
- 3 polyimide, a polybenzoxazole, a polybenzimidazole, a polybenzothiazole, and
- 4 combinations thereof, and wherein the cured polymer first film is in a film-to-
- 5 substrate thickness ratio selected from about one-tenth, one-eighth, one-fifth, one-
- 6 fourth, one-third, and one-half the thickness of the substrate.
- 1 20. The process of claim 14, wherein subsequently thermal curing is carried out
- 2 under conditions to heat the first polymer at greater rate than the substrate.
- 1 21. A method comprising:
- 2 assembling a die to a mounting substrate, wherein the mounting substrate
- 3 includes:

4	a first thermally imprinted cured polymer first film disposed upon a
5	substrate; and
6	a subsequently thermally imprinted cured polymer subsequent film
7	disposed over the first cured polymer first film.

- 1 22. The method of claim 21, wherein assembling a die to a mounting substrate is
- 2 selected from assembling a processor to a mother board, assembling a processor to a
- 3 mezzanine board, assembling a processor to an expansion card, assembling a
- 4 memory chip to a board, assembling a digital signal processor to a board,

disposed over the first cured polymer first film.

- 5 assembling a micro-controller to a board, assembling an application specific
- 6 integrated circuit to a board, and combinations thereof.
- 1 23. The method of claim 21, wherein the cured polymer first film includes a first
- 2 topology that exposes a portion of the substrate, wherein a first metallization is
- 3 disposed within a recess in the first topology; wherein the cured polymer second
- 4 film includes a second topology, wherein a subsequent metallization is disposed
- 5 within a recess in the subsequent topology, the method further including:
- 6 forming an electrical bump in contact with the subsequent metallization; and 7 coupling the electrical bump with the die.
- 1 24. The method of claim 21, wherein the first thermally imprinted polymer
- is imprinted under conditions to increase the glass transition temperature 2
- 3 (T_G) of the first polymer, and wherein the subsequently thermally
- imprinted polymer is imprinted under conditions to increase the T_G of the 4
- 5 subsequent polymer.
- 25. 1 An intermediate system comprising:
- 2 a substrate at a substrate temperature;
- 3 a cured polymer first film at a first glass transition temperature (T_G); and
- 4 an intermediate polymer second film at a second T_G, wherein the cured

- 5 polymer second film is disposed above and on at least a portion of the
- 6 cured polymer first film, and wherein the second T_G is less than the first T_G .
- 1 26. The intermediate system of claim 25, wherein the cured polymer first
- 2 film is selected from a resin, a cyanate ester, a polyimide, a
- 3 polybenzoxazole, a polybenzimidazole, a polybenzothiazole, and
- 4 combinations thereof.
- 1 27. The intermediate system of claim 25, wherein the cured polymer first
- 2 film is in a film-to-substrate thickness ratio selected from about
- 3 one-tenth, one-eighth, one-fifth, one-fourth, one-third, and one-half
- 4 the thickness of the substrate.
- 1 28. A structure comprising:
- 2 a substrate:
- a cured polymer first film disposed above the substrate, wherein the cured
- 4 polymer first film exhibits a first topology, and a minimum feature within the first
- 5 topology, and wherein the minimum feature exhibits a deviation from planarity of
- 6 10 percent or less; and
- a cured polymer second film disposed above and on the cured polymer
- 8 first film, wherein the cured polymer second film exhibits a second topology.
- 1 29. The structure of claim 28 further including:
- 2 an electronic device electrically coupled to the structure.
- 1 30. The structure of claim 28, further including:
- an electronic device electrically coupled to the structure, wherein the
- 3 structure is disposed in one of a computer, a wireless communicator, a
- 4 hand-held device, an automobile, a locomotive, an aircraft, a watercraft, and a
- 5 spacecraft.